

00684.103107

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10/529892

PCT
PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Natsuhiko MIZUTANI et al.

Application No.: 10/529,892 ✓

Entry into U.S. National

Stage Under 35 U.S.C. § 371: April 1, 2005

For: NEAR-FIELD LIGHT GENERATING
METHOD, NEAR-FIELD EXPOSURE
MASK, AND NEAR-FIELD EXPOSURE
METHOD AND APPARATUS

)
: Examiner: Unassigned
)
: Group Art Unit: Unassigned
)
: Confirmation No.: 7800
)
: November 7, 2005
)
:)

Mail Stop Amendment

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Sir:

In compliance with the duty of disclosure under 37 C.F.R. § 1.56 and in accordance with the practice under 37 C.F.R. §§ 1.97 and 1.98, the Examiner's attention is directed to the documents listed on the enclosed PTO-1449 form. A copy of the Japanese patent document (with English language abstract) and a copy of the non-patent document are also enclosed.

Japanese patent document number 8-179493 is discussed on pages 2-3 of the subject specification.

U.S. Patent No. 6,171,730 is discussed on page 3 of the subject specification.

U.S. Patent Nos. 6,304, 527 B1, 5,973,316, and 4,659,429, U.S. Patent Application Publication No. 2002/031299 A1, and Fang Chen et al. "A study of near-field aperture geometry effects on very small aperture lasers (VSAL)" were cited in an International Search Report, which was mailed on March 23, 2005, from the European Patent Office in corresponding

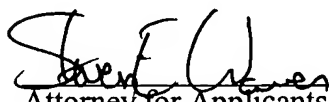
International Application No. PCT/JP2004/014445. Copies of the International Search Report and Written Opinion mailed March 23, 2005 are also enclosed.

Applicants request that the above information be considered by the Examiner and that a copy of the enclosed PTO-1449 form be initialed and returned indicating that such information has been considered.

This Information Disclosure Statement is being filed before the issuance of a first Office Action on the merits. Therefore, no fee under 37 C.F.R. 1.97(c)(2) is believed due. Nevertheless, the Commissioner may charge Deposit Account No. 06-1205, should any fee be due for filing this paper.

Applicants' undersigned attorney may be reached in our Washington D.C. office by telephone at (202) 530-1010. All correspondence should continue to be directed to our address given below.

Respectfully submitted,



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FORM PTO 1449 (modified)		ATTY DOCKET NO. 00684.103107		APPLICATION NO. 10/529,892	
U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		APPLICANT Natsuhiko MIZUTANI et al.			
LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary)		FILING DATE April 1, 2005		GROUP Unassigned	
November 7, 2005					
U.S. PATENT DOCUMENTS					
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS SUBCLASS FILING DATE IF APPROPRIATE
		US 6,171,730 B1	01/09/2001	Kuroda et al.	430 5
		US 5,973,316	10/26/1999	Ebbesen et al.	250 216
		US 6,304,527 B1	10/16/2001	Ito et al.	369 44.23
		2002/0031299 A1	03/14/2002	Hatakoshi	385 31
		US 4,659,429	04/21/1987	Isaacson et al.	156 644
FOREIGN PATENT DOCUMENTS					
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS SUBCLASS TRANSLATION YES/NO/ OR ABSTRACT
		8-179493	07/12/1996	Japan	Abstract
OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)					
		International Search Report mailed March 23, 2005, issued in International Application No. PCT/JP2004/014445.			
		Written Opinion mailed March 23, 2005, issued in International Application No. PCT/JP2004/014445.			
		Chen, Fang, et al., "A Study of Near-field Aperture Geometry Effects on Very Small Aperture Lasers (VSAL)," Proceedings of the SPIE - The International Society For Optical Engineering, Vol. 5069, No. 1, September 16, 2003, pp. 312-318.			
EXAMINER		DATE CONSIDERED			

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.